

# Electrocatalytic reduction of hydrogen peroxide at nanostructured copper modified electrode

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**Abstract** The electrocatalytic reduction of hydrogen peroxide ( $\text{H}_2\text{O}_2$ ) has been studied at nanostructured copper ( $\text{Cu}_{\text{nano}}$ ) modified glassy carbon ( $\text{GC}/\text{Cu}_{\text{nano}}$ ) electrode in phosphate buffer (pH 7.2). The electrical properties of  $\text{GC}/\text{Cu}_{\text{nano}}$  modified electrodes were studied by electrochemical impedance spectroscopy (EIS). Surface and electrochemical characterization were carried out by using atomic force microscopy (AFM) and cyclic voltammetry. A well-defined  $\text{H}_2\text{O}_2$  reduction signal, which is due to mediation of a surface active site redox transition exhibits at the  $\text{GC}/\text{Cu}_{\text{nano}}$  electrode. The  $\text{Cu}_{\text{nano}}$  is acting as a bridge without the aid of any other electron mediator, which enables the direct electron transfer between the modified electrode and the substrate. The results are compared with bulk copper macroelectrode and emphasized the efficiency of the  $\text{Cu}_{\text{nano}}$  modified electrode. Systematic investigations were made to optimize the experimental parameter, such as applied potential ( $E_{\text{app}}$ ) for copper electrodeposition. The calibration curve obtained from chronoamperometric studies was found to be linear in the range 0.5 to 8.0  $\mu\text{M}$   $\text{H}_2\text{O}_2$  with a detection limit of ca. 10 nM ( $S/N = 3$ ) at the  $\text{GC}/\text{Cu}_{\text{nano}}$  electrode. The modified electrode is stable for 1 week in phosphate buffer after repetitive measurements.

**Keyword** Nanostructured copper · Modified electrode · Hydrogen peroxide · Electrocatalysis · Sensors

## 1 Introduction

The assembly of metal nanoparticles into ordered two-dimensional and three-dimensional superstructures has become an interesting aspect in sensors, catalysis, etc. [1–9]. To realize such nanostructures-based materials, it is necessary to design some methods to orient and integrate the nanomaterials in the surface-confined device architecture. The nanosized metal particles mediate the chemical reaction and provide better electrocatalytic activity in chemical sensor applications. A metal complex attached on the surface of the electrode using an irreversibly adsorbed ligand has been explored for the purpose of electrocatalytic reduction of  $\text{H}_2\text{O}_2$  [10–12], which is fundamentally important for low-cost catalyst development in energy devices such as fuel cells. To increase the robustness and durability, a variety of electrode materials, such as graphite carbon paste, polypyrrole, sol-gel and prussian blue and mediators suitable for peroxidase-based electrodes have been reported [13–17]. Nevertheless, the stability and fouling of the materials is a serious problem in using these electrodes [18, 19]. Most of the mediators and metal complexes are unstable at higher pH and hence have a limited working pH range. The  $\text{H}_2\text{O}_2$  biosensor based on horseradish peroxidase immobilized on colloidal gold was found to be electrocatalytically active in the reduction of  $\text{H}_2\text{O}_2$  without using an electron transfer mediator [20]. As this method has paved the way for the construction of third generation mediator-free chemical sensor and there has been considerable interest in fabricating  $\text{H}_2\text{O}_2$  sensor based on metal nanoparticles modified electrodes [18, 21–29]. Modification of carbon electrode with conductive metallic oxides was reported earlier [29, 30].

Electrochemical investigations of  $\text{H}_2\text{O}_2$  reduction using polycrystalline copper electrode have been documented

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[30–32]. The importance of  $\text{H}_2\text{O}_2$  in the overall reduction mechanism of oxygen on copper electrode was pointed out in the early work of Delahay [33]. The convenience of studying the electrochemical behavior of  $\text{H}_2\text{O}_2$  in the absence of oxygen for understanding the overall reduction of  $\text{H}_2\text{O}_2$  at corroding metals has been stressed previously [34]. However, so far this property has rarely been used for analytical applications. Recently, copper electrochemistry has been studied and summarized [35], which shows that a surface activated copper might play an important role in the electrocatalysis of organic compounds. This work deals with the fabrication a high precision and inexpensive analytical method for the electrocatalytic reduction of  $\text{H}_2\text{O}_2$ . In the present study, we first illustrate the preparation of nanostructured copper on glassy carbon electrode followed by measuring its impedance changes. Then, we present the electrocatalytic phenomena of this modified electrode to assess the amplified current signal and the result was compared to bulk copper electrode.

## 2 Experimental

All chemicals were of analytical-reagent grade from Merck. Fresh solution of  $\text{H}_2\text{O}_2$  was prepared in the working buffer and stored in dark at  $<4^\circ\text{C}$ . Copper sulphate, sodium perchlorate, monosodium and disodium hydrogen phosphate (Merck) were used as received. 0.1 M phosphate buffer (pH 7.2) was used in the experiment. All aqueous solution has been prepared in de-ionized double distilled water. When anaerobic conditions were chosen, purified nitrogen gas was used to expel the dissolved oxygen.

All the electrochemical experiments were performed in an EG&G PAR model 283 potentiostat/galvanostat controlled by Echem software loaded personnel computer. The electrochemical measurements were carried out in a two-compartment three-electrode system consists of a platinum wire as the counter electrode, standard calomel electrode as the reference electrode and glassy carbon (GC) as the working electrode ( $0.07\text{ cm}^2$ ). The electrochemical impedance spectroscopy (EIS) analyses were performed using CHI 650B potentiostat (CH Instruments, Inc., TX, USA). The surface image of nanostructured copper was studied on Indium Tin Oxide (ITO) electrode. The surface images of copper macroelectrode and nanostructured copper were measured by atomic force microscopy (AFM) using the Shimadzu SPM 9500 scanning probe microscope (AFM analysis) with Nanoscope IIIa controller. The gold cantilever diameter in AFM measurement is  $50\ \mu\text{m}$ .

The nanostructured copper ( $\text{Cu}_{\text{nano}}$ ) was deposited electrochemically on GC electrode using a solution of 0.01 M  $\text{CuSO}_4$  and 0.1 M  $\text{NaClO}_4$  at an applied potential of  $-0.4\text{ V(SCE)}$ . For comparison, nanostructured copper was

deposited at different applied potential between  $-0.1$  and  $-0.6\text{ V(SCE)}$ . Under these conditions, the charge consumed during nanostructured copper loading was calculated as  $0.011\text{ C cm}^{-2}$ . Prior to every experiment, the electrodes were polished with an aqueous suspension of 1.0 and  $0.05\ \mu\text{m}$  alumina on a Buehler cloth, rinsed copiously with doubly distilled water and sonicated in a water bath for 3 min followed by activation to remove the charging current.

## 3 Results and discussion

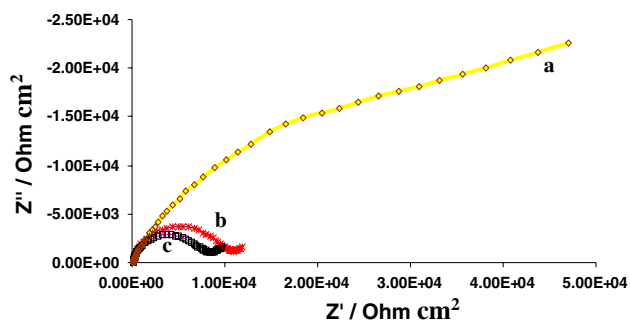
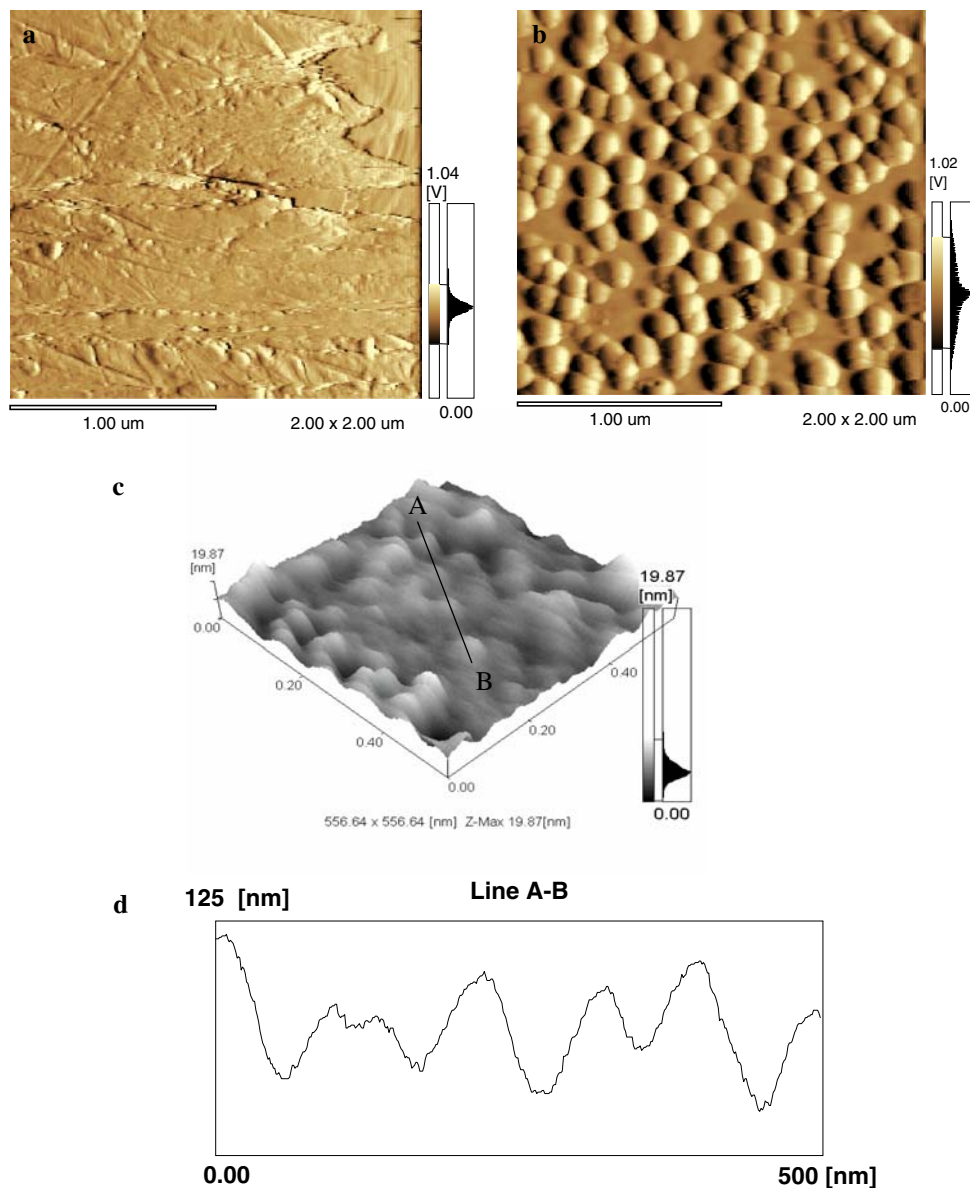
### 3.1 Surface analysis of bulk copper and ITO/ $\text{Cu}_{\text{nano}}$ electrodes by atomic force microscopy (AFM)

Figure 1 shows the AFM images of bulk copper (copper macroelectrode) and ITO/ $\text{Cu}_{\text{nano}}$  electrodes. The AFM image of a bulk copper has been recorded (Fig. 1a) to compare its morphology and roughness with the surface of ITO/ $\text{Cu}_{\text{nano}}$  electrode (Fig. 1b). The bulk copper electrode depicts no characteristic observation compared to ITO/ $\text{Cu}_{\text{nano}}$  electrode. Two-dimensional AFM image of ITO/ $\text{Cu}_{\text{nano}}$  electrode ( $\text{Cu}_{\text{nano}}$  electrodeposited at  $-0.4\text{ V}$ ) is shown in Fig. 1b. It clearly emphasized many spherical  $\text{Cu}_{\text{nano}}$  have formed on the ITO surface. The diameter of the spherical nanostructures is in the range of 50–150 nm. As shown in Fig. 1b, a high-coverage of non aggregated  $\text{Cu}_{\text{nano}}$  was observed. Figure 1c shows the three-dimensional AFM image of nanostructured copper on the electrode surface. The average grain size is about 95 nm with a roughness factor of 92.74 nm (Rq) which is confirmed in the cursor plot (Fig. 1d) acquired from Fig. 1c. The particle size is not precise apparently due to the surface oxides which are known for their ability to destabilize particle size and other properties [36, 37]. The electrodeposition of copper at  $-0.4\text{ V}$  leads to the formation of nanostructured copper with homogeneous distribution on the electrode surface and majority of structures remains close to adjacent ones.

### 3.2 Electrochemical impedance spectroscopy (EIS)

EIS is used to investigate the impedance changes at the  $\text{Cu}_{\text{nano}}$  modified electrode. It is an effective electrochemical technique for probing the features of surface modified electrodes [38, 39]. EIS measurements have been performed to characterize the interfacial properties of bulk copper electrode, bare glassy carbon electrode (GC) and nanostructured copper modified GC electrode (GC/ $\text{Cu}_{\text{nano}}$ ) ( $\text{Cu}_{\text{nano}}$  was electrodeposited at  $-0.4\text{ V}$ ). Figure 2 shows the Nyquist plot of the EIS for bulk copper electrode, bare GC and GC/ $\text{Cu}_{\text{nano}}$  electrode in the presence of equimolar  $[\text{Fe}(\text{CN})_6]^{3-/4-}$  in 0.1 M phosphate buffer. The

**Fig. 1** Tapping mode of two-dimensional AFM images of bulk Cu electrode (a), ITO/Cu<sub>nano</sub> electrode (b) and three-dimensional AFM image of ITO/Cu<sub>nano</sub> electrode (c). (Cu<sub>nano</sub> electrodeposited at -0.4 V (SCE)). Cursor plot (d) was obtained for the line A–B shown in Fig. 1c



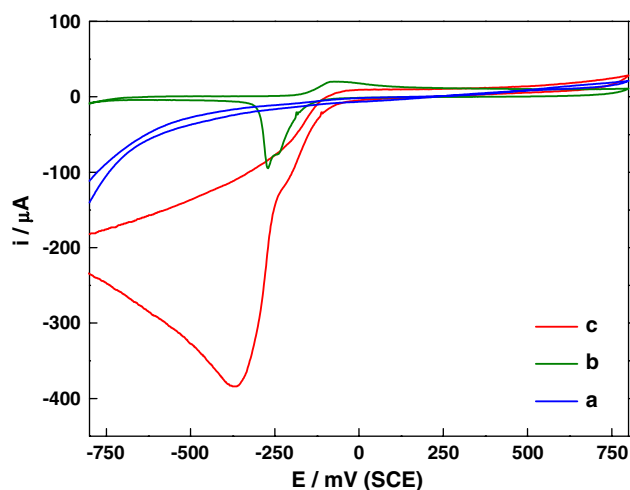
**Fig. 2** Electrochemical impedance spectra of (a) bulk Cu, (b) bare GC and (c) GC/Cu<sub>nano</sub> electrodes in 0.1 M phosphate buffer (pH 7.2) and 1 mM K<sub>3</sub>[Fe(CN)<sub>6</sub>]/K<sub>4</sub>[Fe(CN)<sub>6</sub>]. Applied potential: 0.2 V and frequency range: 1 Hz–100 kHz

perturbation voltage was 0.2 V and the frequency range was 1 Hz–100 KHz. The semicircle diameter equals the charge transfer kinetics of the redox-probe at the electrode interface, where  $Z_{re}$  and  $Z_{im}$  are real and imaginary parts of impedance ( $Z$ ). As shown in curve a, a very large charge transfer resistance ( $R_{ct}$ ) was observed for  $[Fe(CN)_6]^{3-/4-}$  couple at bulk copper electrode (Cu wire, diameter 0.3 cm). The pretreated bare GC and GC/Cu<sub>nano</sub> electrodes showed a decreased  $R_{ct}$  of 12 K $\Omega$  cm<sup>2</sup> (curve b) and 8 K $\Omega$  cm<sup>2</sup> (curve c), respectively. The semicircle plot is probed by higher frequencies, which means that the dynamics of electron transfer in higher frequency range is observed and the current due to voltage excitation is under kinetic control. The low frequency region, where the slope of  $Z_{re}$  vs.

$Z_{im}$  is unity, is dominated by mass region [40]. It could be observed that the diameter of the semicircle plot was decreased with the modified process of the GC electrode. The semicircle of curve b was remarkably smaller than curve a. This obvious change indicates the pretreated GC electrode accelerates electron transfer of the probe molecule. The semicircle of curve c was even smaller than the nanostructured copper facilitated the electron-transfer process on the electrode surface. Hence, it is clear that the GC/Cu<sub>nano</sub> modified electrode is more suitable for electrochemical sensing due to its smaller electron transfer resistance. It is consistent with the cyclic voltammetry results obtained toward H<sub>2</sub>O<sub>2</sub> reduction (*vide infra*).

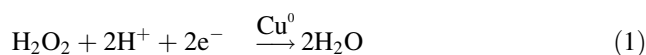
### 3.3 Electrocatalytic reduction of H<sub>2</sub>O<sub>2</sub> at GC/Cu<sub>nano</sub> electrode

The bare GC electrode shows no characteristic behavior between 0.8 and −0.8 V in the presence of H<sub>2</sub>O<sub>2</sub> in 0.1 M phosphate buffer (pH 7.2) (Fig. 3a). This phenomenon interprets that H<sub>2</sub>O<sub>2</sub> reduction could not be achieved at bare GC electrode. Figure 3b and c show the cyclic voltammograms of GC/Cu<sub>nano</sub> electrode (electrodeposited at −0.4 V) in the absence and presence of H<sub>2</sub>O<sub>2</sub> in 0.1 M phosphate buffer. A cathodic peak (Fig. 3b) at −0.28 V due to Cu<sup>I</sup>O reduction to Cu<sup>0</sup> and an anodic peak at −0.08 V due to Cu<sup>0</sup> oxidation were observed at GC/Cu<sub>nano</sub> electrode. The presence of copper and copper oxides on the surface of the electrode was confirmed by cyclic voltammetric result [41]. Our interest is to utilize this nanostructured copper electrode in the electrocatalytic application.



**Fig. 3** CV recorded for  $9 \times 10^{-5}$  M H<sub>2</sub>O<sub>2</sub> in 0.1 M phosphate buffer at bare GC electrode (a). CVs recorded at GC/Cu<sub>nano</sub> electrode in the absence (b) and presence (c) of  $9 \times 10^{-5}$  M H<sub>2</sub>O<sub>2</sub> in 0.1 M phosphate buffer (Cu<sub>nano</sub> electrodeposited at −0.4 V). Scan rate = 50 mVs<sup>−1</sup>

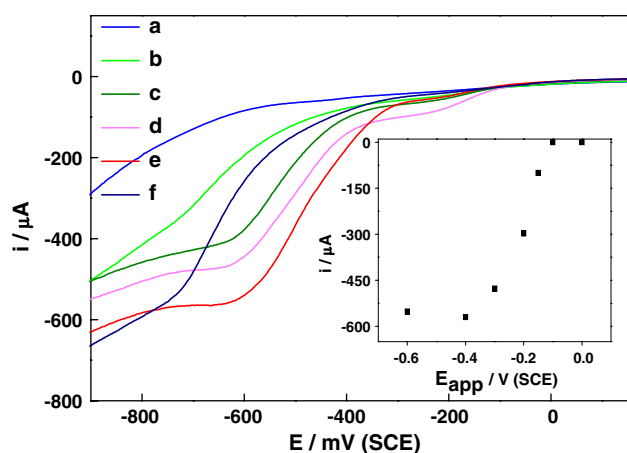
In the presence of H<sub>2</sub>O<sub>2</sub>, GC/Cu<sub>nano</sub> electrode shows a remarkably enhanced reduction peak current starting from −0.1 V (Fig. 3c). This indicates that the H<sub>2</sub>O<sub>2</sub> reduction could be observed at the GC/Cu<sub>nano</sub> electrode. In the GC electrode, Cu<sub>nano</sub> mediates the direct electron transfer leading to the H<sub>2</sub>O<sub>2</sub> reduction and improved its electrocatalytic activity at this modified electrode. The H<sub>2</sub>O<sub>2</sub> reduction peak has been observed at −0.3 V (Fig. 3c) which follows a two-electron and two-proton reaction (Eq. 1) [18].



When compared to earlier reports on H<sub>2</sub>O<sub>2</sub> reduction at different electrodes [10–12, 20], it is apparent that overpotential has decreased by about 100–400 mV. In addition, H<sub>2</sub>O<sub>2</sub> reduction current is also enhanced at the GC/Cu<sub>nano</sub> electrode which shows Cu<sub>nano</sub> acts as the catalytic center and mediates the reaction. The absence of specific peak in the anodic scan indicates that the H<sub>2</sub>O<sub>2</sub> oxidation is not a favorable reaction at the GC/Cu<sub>nano</sub> electrode. In this system, the nanostructured copper exhibits a metastable active surface redox transition, which is of major impact in both electrocatalytic and electrodeposition viewpoint [42]. In addition, the nature of this transition is not well understood and it apparently functions as redox mediator [43, 44], which dominates in the electrocatalytic behavior of this electrode system. It is worth mentioning here that, despite extensive worldwide investigation, the chemical behavior of surface active sites in general is not well established and is largely a matter of speculation. Active state behavior of metal surface is very difficult to investigate as the species involved are of quite low coverage and unstable (or metastable).

### 3.4 Influence of E<sub>app</sub> on the electrodeposition of Cu<sub>nano</sub> and its effect on H<sub>2</sub>O<sub>2</sub> reduction

Copper was electrochemically deposited on the GC electrode by using 0.01 M CuSO<sub>4</sub> and 0.1 M NaClO<sub>4</sub> at different applied potential (E<sub>app</sub>) ranging from 0.0 to −0.6 V(SCE). Under these conditions, the charge consumed during Cu<sub>nano</sub> deposition was measured as 0.011 C cm<sup>−2</sup>. It means that the modified electrodes should maintain its charge consumption with respect to different E<sub>app</sub> towards nanostructure formation. In order to analyze the electrocatalytic activity of metastable active state in nanostructured copper electrode, the charge has been maintained during electrodeposition at different E<sub>app</sub>. The GC/Cu<sub>nano</sub> electrodes were prepared at different E<sub>app</sub> such as 0, −0.1, −0.2, −0.3, −0.4, −0.5 and −0.6 V. The above prepared electrodes were used to record cyclic voltammogram in the presence of 0.13 mM H<sub>2</sub>O<sub>2</sub> in 0.1 M phosphate

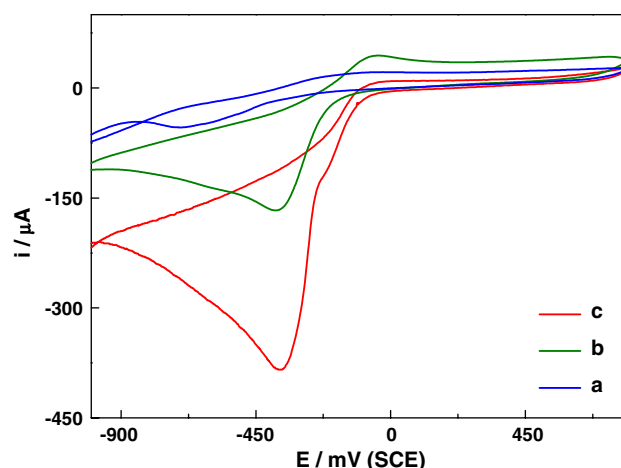


**Fig. 4** Linear sweep voltammograms (LSVs) recorded at GC/Cu<sub>nano</sub> electrode in the presence of 0.13 mM H<sub>2</sub>O<sub>2</sub> in 0.1 M phosphate buffer. GC/Cu<sub>nano</sub> electrode was prepared at different E<sub>app</sub> (a = 0, b = -0.1, c = -0.2, d = -0.3, e = -0.4 and f = -0.5 V). Scan rate = 50 mV s<sup>-1</sup>. Inset: Effect of different E<sub>app</sub> on the formation of Cu<sub>nano</sub> on GC electrode (GC/Cu<sub>nano</sub>) and the corresponding reduction peak current of 0.13 mM H<sub>2</sub>O<sub>2</sub> in 0.1 M phosphate buffer

buffer. Figure 4 shows the linear sweep voltammetric responses observed for 0.13 mM H<sub>2</sub>O<sub>2</sub> at GC/Cu<sub>nano</sub> electrode which prepared in different E<sub>app</sub>. An increase in the H<sub>2</sub>O<sub>2</sub> reduction peak current was observed at GC/Cu<sub>nano</sub> electrode which prepared in different E<sub>app</sub> between 0 and -0.6 V and reached a maximum electrocatalytic activity for the nanostructured copper prepared at -0.4 V (Fig. 4e). The cathodic peak current observed for H<sub>2</sub>O<sub>2</sub> reduction were plotted against E<sub>app</sub> as shown in Fig. 4 (inset). An increase in the electrocatalytic H<sub>2</sub>O<sub>2</sub> reduction peak current was observed at the GC/Cu<sub>nano</sub> electrodes prepared at more negative potential and attained maximum at -0.4 V as shown in Fig. 4(inset). The GC/Cu<sub>nano</sub> electrodes prepared between 0 and -0.4 V show a significant difference in the electrocatalytic behavior (Fig. 4) whereas saturation might be taking place during nanostructured copper deposited at more negative E<sub>app</sub> such as -0.6 V, etc. On the other hand, the electrocatalytic H<sub>2</sub>O<sub>2</sub> oxidation was not observed at the GC electrode. In our earlier report, we explained the deposition of copper structures with respect to different E<sub>app</sub> and explained the importance of copper deposition at more negative potential [45].

### 3.5 Comparative study of H<sub>2</sub>O<sub>2</sub> reduction at bulk copper and GC/Cu<sub>nano</sub> electrode

Figure 5a shows the cyclic voltammogram recorded at bulk copper (copper macroelectrode) in deaerated 0.1 M phosphate buffer. The copper oxide growth appeared at potential positive to -0.25 V underwent reduction at more negative potential in the cathodic scan as shown in Fig. 5a.



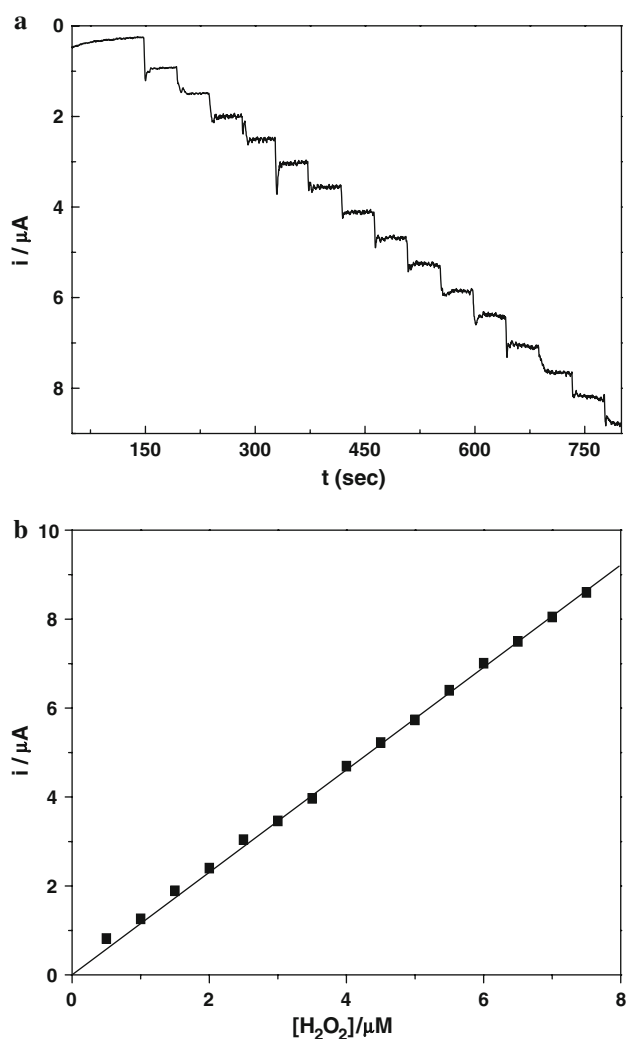
**Fig. 5** CVs recorded at bulk Cu electrode in the absence (a) and presence (b) of  $9 \times 10^{-5}$  M H<sub>2</sub>O<sub>2</sub> and at GC/Cu<sub>nano</sub> electrode in the presence (c) of  $9 \times 10^{-5}$  M H<sub>2</sub>O<sub>2</sub> in 0.1 M phosphate buffer (Cu<sub>nano</sub> electrode deposited at -0.4 V). Scan rate = 50 mV s<sup>-1</sup>

Figure 5b shows the cyclic voltammogram recorded at bulk copper electrode for  $9 \times 10^{-5}$  M H<sub>2</sub>O<sub>2</sub> in 0.1 M phosphate buffer. An increase in the peak current was observed due to H<sub>2</sub>O<sub>2</sub> reduction at the bulk copper electrode (Fig. 5b). Figure 5c shows the cyclic voltammogram recorded at the GC/Cu<sub>nano</sub> electrode for  $9 \times 10^{-5}$  M H<sub>2</sub>O<sub>2</sub> in 0.1 M phosphate buffer. It is evident that the GC/Cu<sub>nano</sub> electrode shows higher catalytic current compared to bulk copper electrode towards H<sub>2</sub>O<sub>2</sub> reduction.

### 3.6 Constant potential amperometric studies

Chronoamperometry is also used to test the applicability of the GC/Cu<sub>nano</sub> modified electrode for the determination of H<sub>2</sub>O<sub>2</sub>. The nanostructured copper electrode deposited at -0.4 V on GC electrode was used as a transducer for the electrocatalytic reduction of H<sub>2</sub>O<sub>2</sub>. Figure 6a shows the chronoamperogram that was recorded at the GC/Cu<sub>nano</sub> electrode in a continuously stirred 0.1 M phosphate buffer (pH 7.2) at an operating potential of -0.5 V. As shown in Fig 6a, during successive additions of 0.5 μM H<sub>2</sub>O<sub>2</sub> at a sampling time of ca. 3 s, a well-defined response was obtained. Figure 6a shows the chronoamperogram recorded in the concentration range between 0.5 and 8 μM H<sub>2</sub>O<sub>2</sub> and corresponding increase in the peak current. Figure 6b depicts that the current varies linearly with the concentration of H<sub>2</sub>O<sub>2</sub> in the range from 0.5 to 8 μM. The sensitivity was found to be  $\sim 1.1 \mu\text{A}/\mu\text{M}$  and the detection limit was calculated based on the  $3\sigma/m$  criterion, where  $\sigma$  and  $m$  represents the blank standard deviation and sensitivity respectively. The detection limit was found to be 10 nM. The response time at each addition of H<sub>2</sub>O<sub>2</sub> is 3 s, which indicates a fast electron transfer process at this modified





**Fig. 6** (a) Current–time response observed for H<sub>2</sub>O<sub>2</sub> at the GC/Cu<sub>nano</sub> electrode after subsequent spiking of 0.5 μM H<sub>2</sub>O<sub>2</sub>. (b) Calibration plot observed for H<sub>2</sub>O<sub>2</sub> at an applied potential of –0.5 V(SCE) in 0.1 M PBS

electrode. The electrode was fairly stable for 1 week when stored at room temperature in phosphate buffer after repetitive measurements and 95% reproducibility was achieved at the GC/Cu<sub>nano</sub> electrode.

#### 4 Conclusions

A simple and robust nanostructured copper modified electrode (GC/Cu<sub>nano</sub>) was prepared by electrochemical method. The cyclic voltammetric results confirm the presence of electrodeposited copper on the GC electrode surface. The size and uniformity of the nanostructured copper were characterized by AFM. In addition, the electrical properties of the Cu<sub>nano</sub> modified electrode were analyzed by EIS. The electrochemical studies showed that

the Cu<sub>nano</sub> electrodeposited at –0.4 V is an excellent electrocatalyst for the reduction of H<sub>2</sub>O<sub>2</sub> in submicromolar concentration. Cu<sub>nano</sub> exhibits an active surface redox transition, which is of major significance in the electrocatalytic reduction of H<sub>2</sub>O<sub>2</sub>. Finally, the sensitivity and the detection limit of H<sub>2</sub>O<sub>2</sub> were highlighted.

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